

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application. Please cancel claims 1-19 and amend claim 20 as follows:

Listing of Claims:

1-19. (Cancelled)

20. (Currently Amended) An apparatus for determining a dimension of a semiconductor device feature, comprising:

first and second sources of electrons;

a first lens positioned proximate to the first source of electrons to receive a first electron beam emitted therefrom;

a second lens positioned proximate to the second source of electrons to receive a second electron beam emitted therefrom;

a ~~port surface plate~~ having a first port and a second port extending through a thickness thereof therethrough, the first port spaced apart from the first lens to receive the first electron beam passing through the first lens, the second port spaced apart from the first port and from the second lens to receive the second electron beam passing through the second lens;

a third lens configured to focus the first electron beam on a first position surface and positioned to receive the first electron beam passing through the first port ;

a fourth lens configured to focus the second electron beam on a second position surface and positioned to receive the second electron beam passing through the second port ; and

a support configured to engage the semiconductor device and located to receive the first and the second electron beams, at least one of the support and the sources of electrons being movable relative to each other ~~the other of the support and the sources of electrons in any of the x, y, or z planes.~~

21. (Original) The apparatus of claim 20 wherein the support is movable relative to the sources of electrons in a direction generally transverse to at least one of the first and second electron beams.

22. (Original) The apparatus of claim 20 wherein the support is movable relative to the sources of electrons in a direction generally aligned with an axis of at least one of the first and second electron beams.

23. (Original) The apparatus of claim 20, further comprising a first detector spaced apart from the support to receive a first flow of electrons from the semiconductor device and generate a first signal corresponding thereto, and a second detector spaced apart from the support to receive a second flow of electrons reflected from the semiconductor device and generate a second signal corresponding thereto.

24. (Previously Presented) The apparatus of claim 23, further comprising a third detector operatively coupled to either the support or one of the sources to detect movement of either the support or one of the sources, the third detector generating a third signal corresponding to movement detected thereby.

25. (Previously Presented) The apparatus of claim 24, further comprising a memory device coupled to at least one of the first, second and third detectors to store the signal generated by the at least one detector.

26. (Previously Presented) The apparatus of claim 24, further comprising a display coupled to at least one of the first, second and third detectors to graphically display a strength of the first and second electron flows as a function of the movement detected by the third detector.

27. (Previously Presented) The apparatus of claim 24, further comprising a printing device coupled to at least one of the first, second and third detectors to print a representation of a strength of the first and second flows of electrons as a function of the movement detected by the third detector.

Claims 28-82. (Cancelled)